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Japanese patent application no. 7-177858, filed July 14, 1995, Japanese patent application no.
6-090837, filed April 28, 1994, and Japanese patent application no. 6-198350, filed August 23,
1994.

IN THE CLAIMS:

Please **AMEND** claim 58, as follows.

58. (ONCE AMENDED) A method for projecting a pattern from a reticle onto a substrate,
comprising:

transmitting light from the reticle through a first imaging system, where the transmitted
light pass through a single-pass lens group and a double-pass lens group to a concave mirror,
and the light is reflected from the concave mirror back through the double-pass lens group
toward the single-pass lens group;

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separating the light propagating through the double-pass lens group to the concave
mirror from the light propagating through the double-pass lens group from the concave mirror;
with the first imaging system, forming an intermediate image of the pattern between the
first imaging system and a second imaging system;

directing the light propagating from the concave mirror through the second imaging
system; and

forming an image of the reticle on the substrate with the second imaging system, wherein
the single-pass lens group includes from objectwise to imagewise, a first negative
lens subgroup, a positive lens subgroup, and a second negative lens subgroup, and
the double-pass lens group includes the concave mirror.